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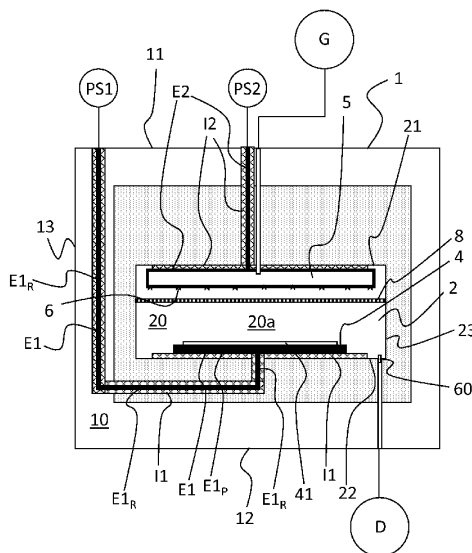


Fig. 1

(57) Abstract: The invention relates to a plasma-enhanced atomic layer deposition apparatus comprising a vacuum chamber (1), a reaction chamber (2) arranged inside the vacuum chamber (1), a substrate holder (4) for supporting a substrate (41), and a showerhead nozzle (5) arranged opposite the substrate holder (4) such that a reaction zone (20a) is formed between the showerhead nozzle (5) and the substrate holder (4) in the reaction space (20), the apparatus further comprising a first power source (PS1) electrically connected to the substrate holder (4), and a second power source (PS2) electrically connected to the showerhead nozzle (5), said first power source (PS1) and second power source (PS2) are arranged outside the vacuum chamber (1).

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